

**Figure. 1** Schematic cross-section view of formation Ta films 1110 on silicon substrate 1100 without buffer (Figure 1(a)) and with buffer layer 1120 (Figure 1(b)).(Narayan)

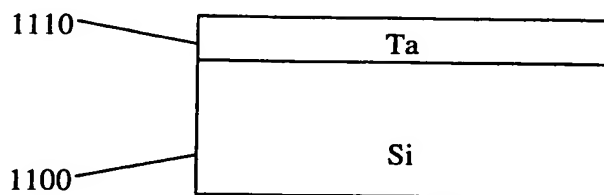


Fig. 1 (a)

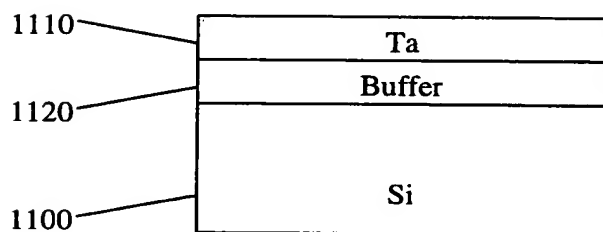


Fig. 1 (b)

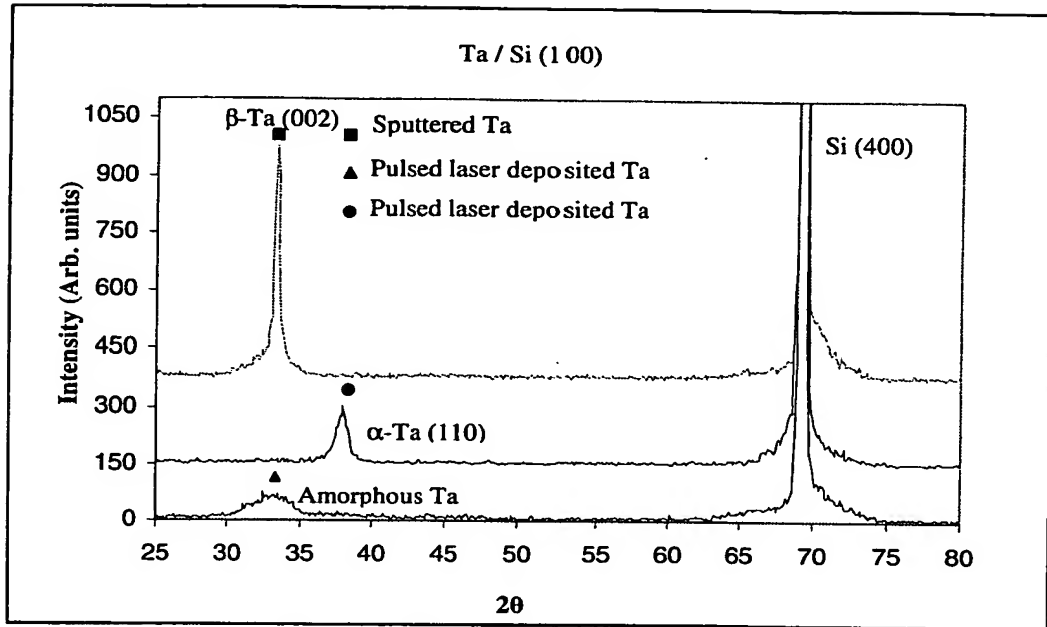
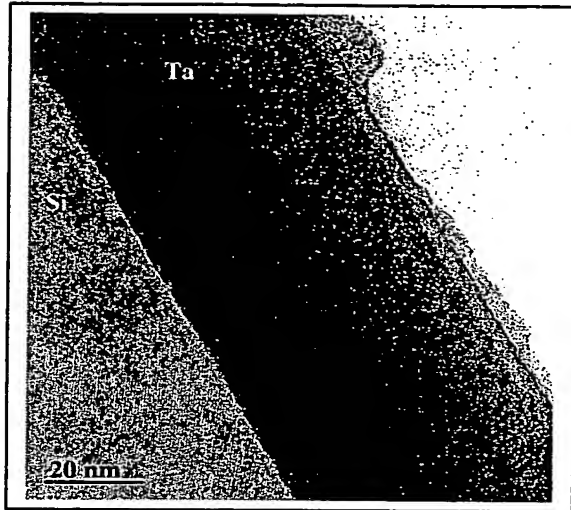
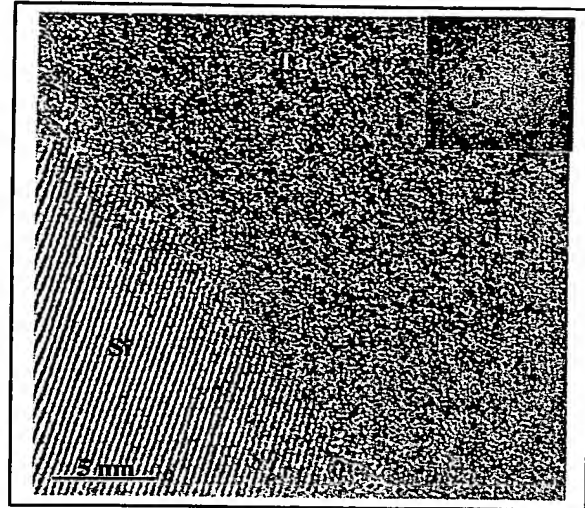


Fig. 2. Narayan

METHODS OF FORMING ALPHA AND BETA TANTALUM FILMS  
WITH CONTROLLED AND NEW MICROSTRUCTURES



(a)



(b)

Fig. 3.Narayan.

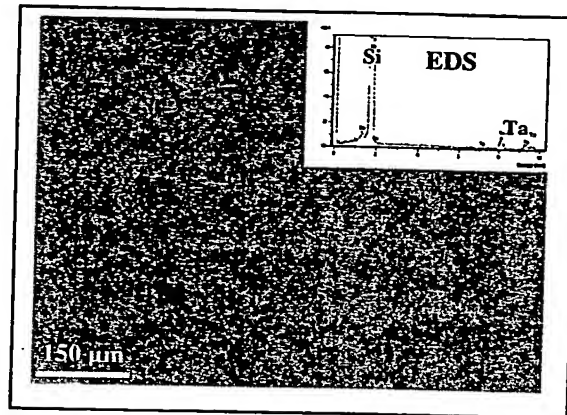


Fig. 4. Narayan

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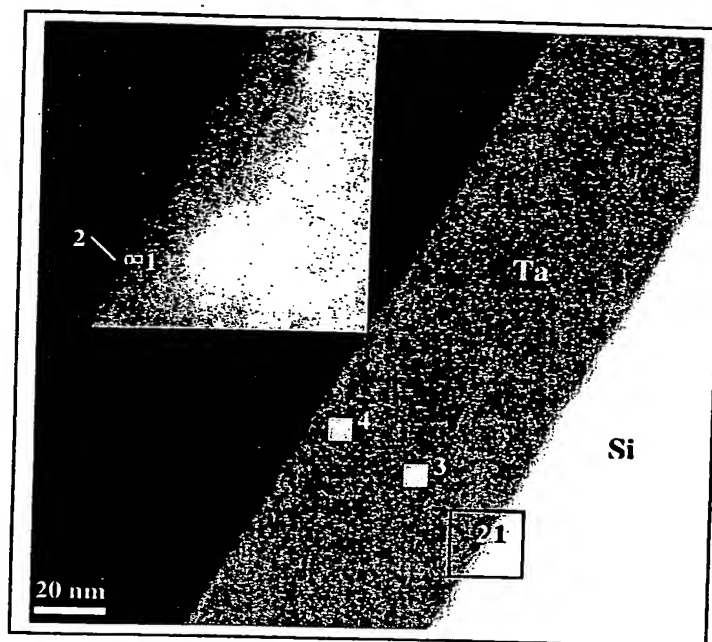


Fig. 5. (a) Narayan

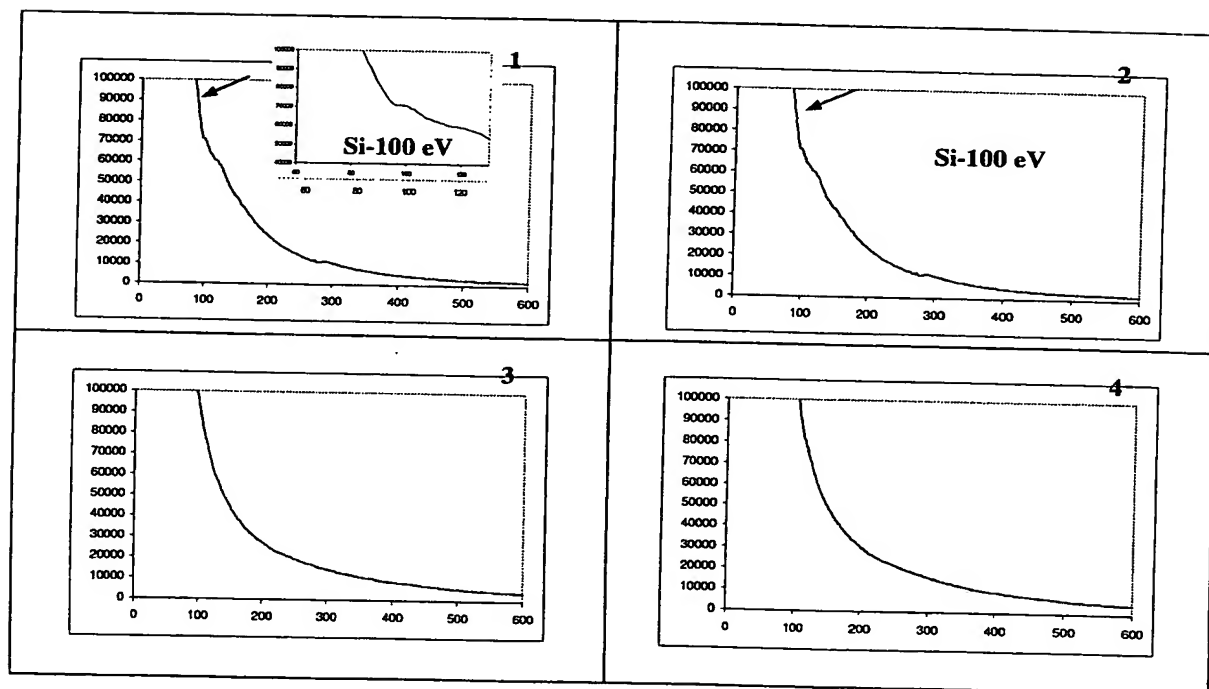


Fig. 5 (b) Narayan

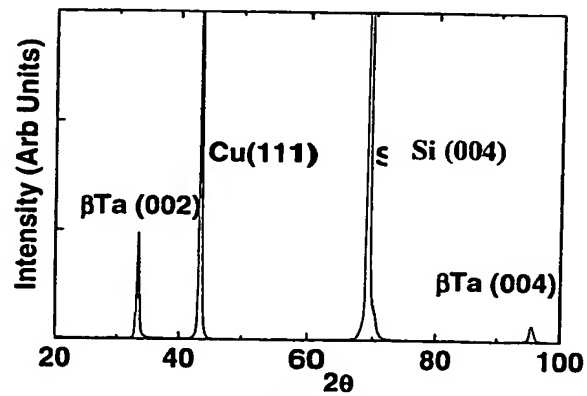


Fig. 6. (a) Narayan

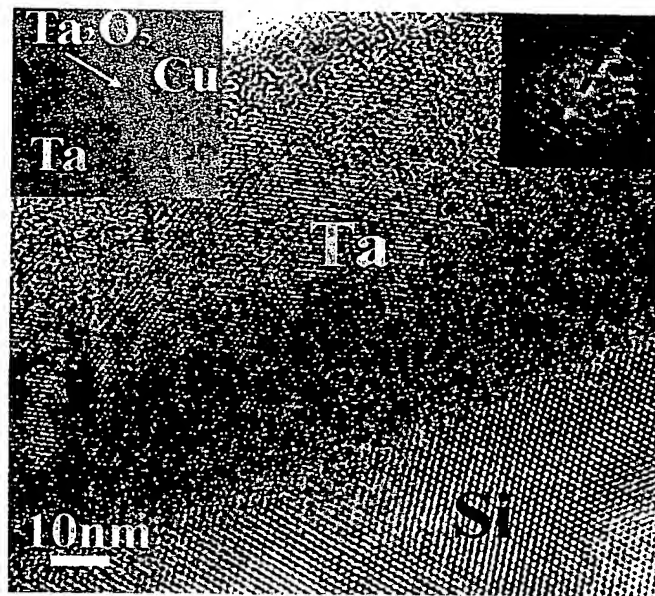


Fig. 6. (b) Narayan

Figure 7(a) Narayan

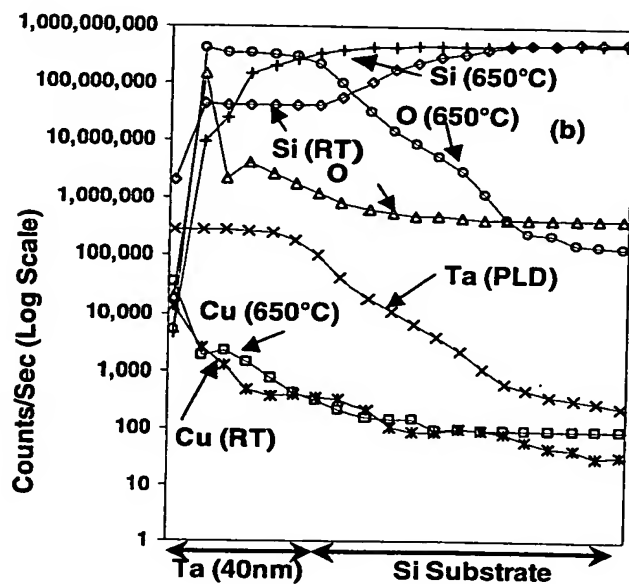
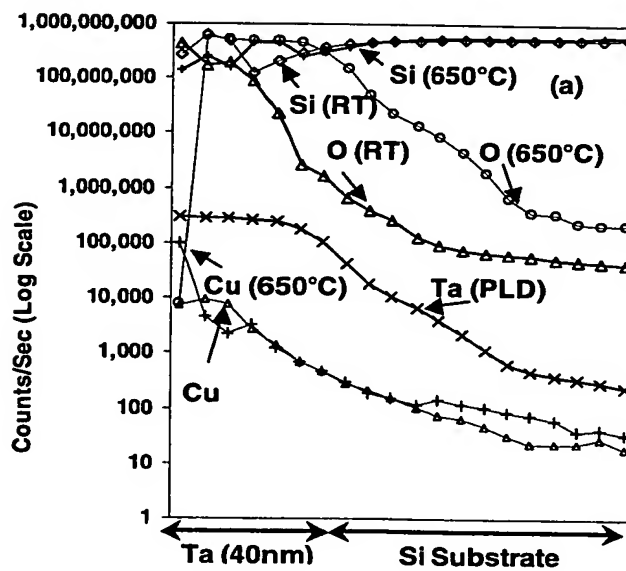


Figure 7(b) Narayan



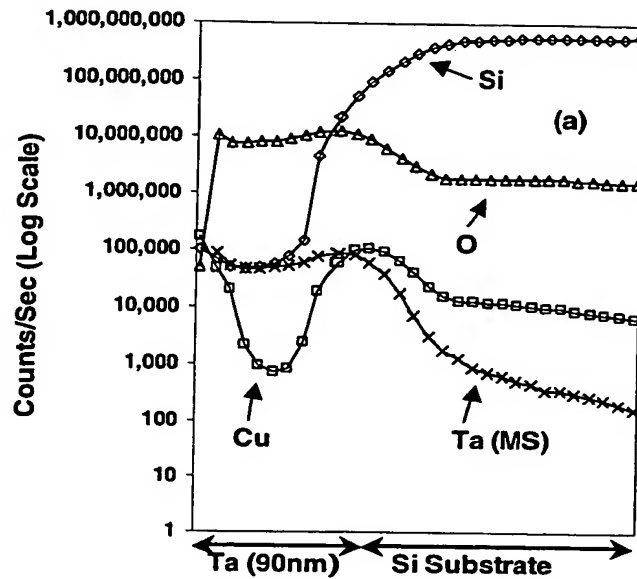


Fig. 8. (a) Narayan

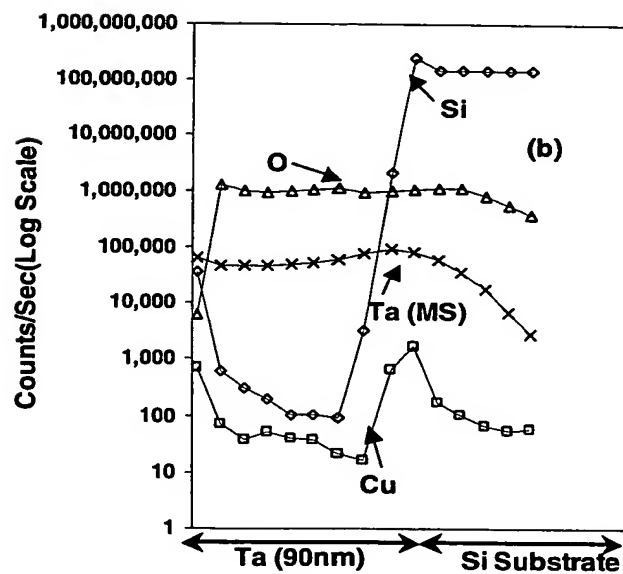


Fig. 8. (b) Narayan



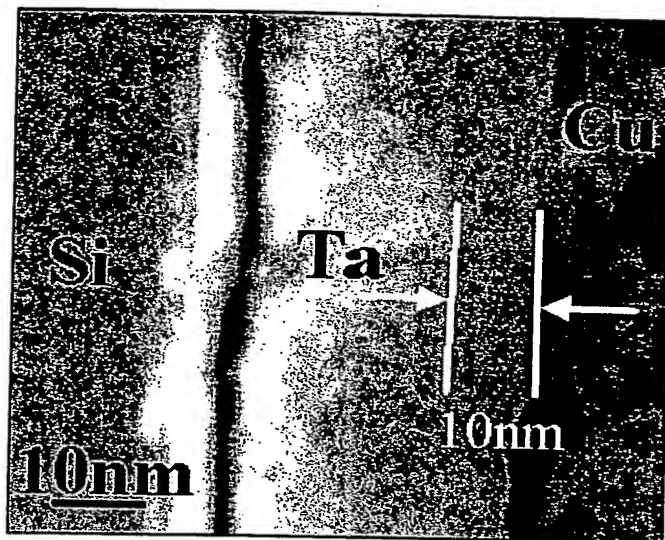


Fig. 9(a). Narayan

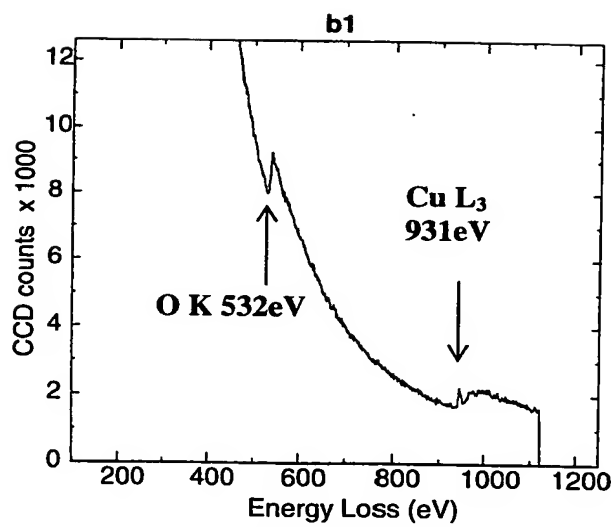


Fig. 9. (b) Narayan

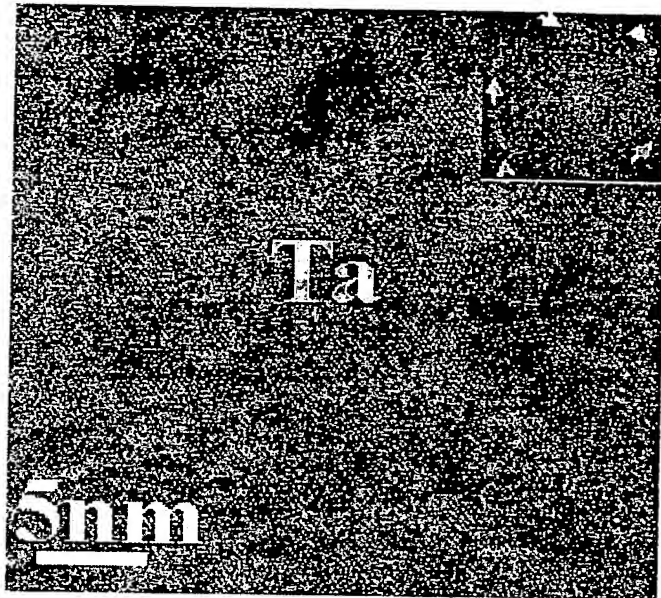


Fig. 10. Narayan

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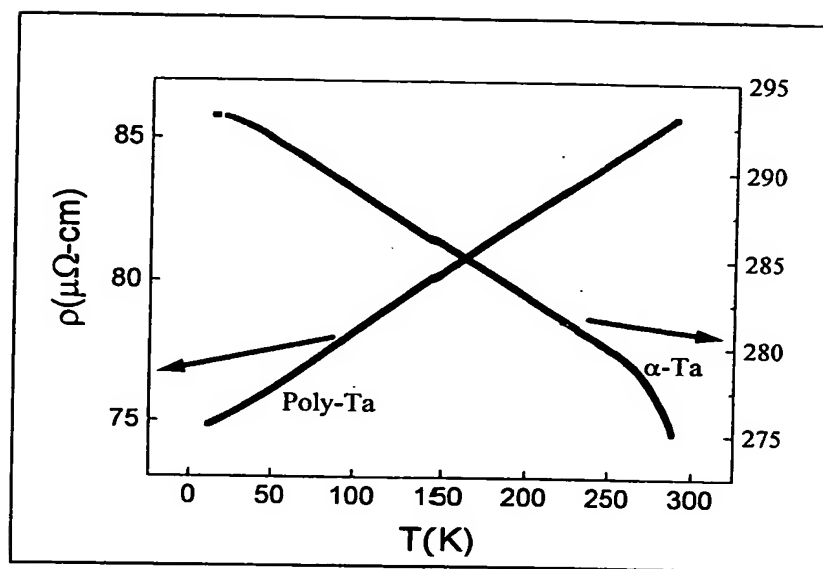


Fig. 11. Narayan

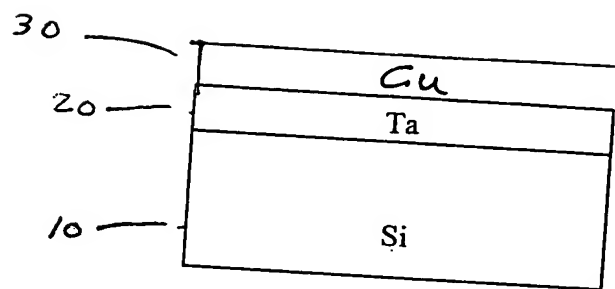


Fig. 12 (a)

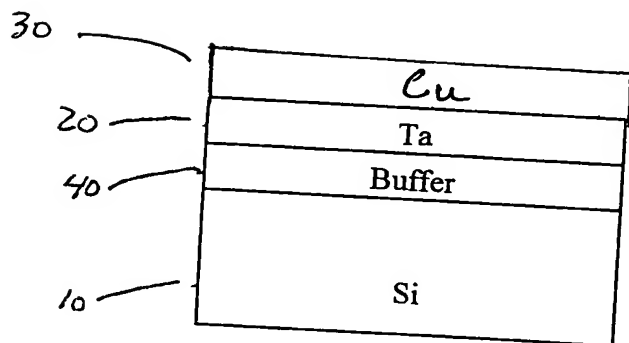


Fig. 12 (b)